



Department of Electronics (School of Physical Sciences)

Materials and Devices Laboratory for Nanoelectronics (MDLN)

Class 10K Clean Room

Announces

30 Hrs Hands-on Training Course for Industry Professionals and Academicians on "Fabrication of Nano-Scale Semiconductor Devices" in Class 10000 Clean Room

[also suitable for Engineering / Science Students as a Skill Enhancement Course, towards NEP-2020 Implementation]

About Course

This **30 Hrs Hands-on Training Course on "Fabrication of Nano-Scale Semiconductor Devices" in Class 10k Clean Room** is a specialized skill enhancement program designed to provide in-depth knowledge and practical experience in the field of semiconductor technology, with a specific focus on Metal Oxide Semiconductor (MOS) devices fabrication and characterization. The course will be extremely useful for Industry Professionals from R&D, Product Development and Manufacturing department manufacturing and academia.

Course Contents:

- ❖ Introduction and overview of semiconductor device fabrication, MOS Structure, clean room design, classification & Importance.
- ❖ Basics of fabrication process: Semiconductor wafer Cleaning (RCA), Oxidation, Doping, Etching, metallization, Annealing etc.
- ❖ Introduction to fabrication systems such as PEALD, RTP, Thermal Evaporation etc.
- ❖ Characterization Techniques like FTIR, Ellipsometry, Elemental & Electrical Characterization: IV-CV Setup
- ❖ Introduction to Lithography: Basics and types of Lithography.

Course Outcome:

- Participants will get hands-on training on various nano scale Device Fabrication systems in class **10K Clean Room**
- They will fabricate nano scale devices by their own (prototype) on Si wafer.
- They will get certification of course completion (2 credits) by KBCNMU, Jalgaon

Intended participants:

Professionals from various industries, academic faculty members, and research students with diverse backgrounds encompassing fields such as Electronics, Electronics & Telecommunication (E & TC), Instrumentation, Metallurgy, Chemical Technology, Material Science, Physics, and Chemical Science, are invited to participate. Additionally, interested undergraduate and postgraduate engineering and science students may have the opportunity to join at a subsidized rate.

Course Fees Structure and Registration Link

- ❖ Rs 30,000/- for Industry Participants
- ❖ Rs 20,000/- for Faculties from Academia
- ❖ Rs 12,000/- for UG/PG/PhD students of Engineering and Science (students @ subsidized rates) *(Note: fees included for cost of clean room garment kit and Silicon wafer, allied chemicals & precursors etc.)*

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- ❖ Rs 2,000/- (extra for Accommodation on campus)
- ❖ Important dates:

Registration open till : 05/09/2023

Commencement date: 11/09/2023

Note: 10% Discount in course fees may be given to the group booking of 10 student.



Registration Link: <https://forms.gle/G44GryPrmBAj3w6d7>

Organizing Team:

- ❖ Prof. A. M. Mahajan (Senior Professor and Director, SOPS)
- ❖ Dr. D. J. Shirale (Assistant Professor)
- ❖ Mr. Vaibhav Borokar (Researcher)
- ❖ Mr. M. S. Netkar (Technical Assistant)

For more information contact:

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20 Seats only



Nano Scale Device

Hands-on Training Session :

Process Details	Day 1	Day 2	Day 3	Day 4	Day 5
Introduction to various Clean room components, protocols, Chemical Treatment Bench (CTB) and familiarization. 2 inch Si wafer handling, cleaning (RCA) process by using CTB,	A1	A5	A4	A3	A2
Deposition of High-k (La_2O_3) ultra thin Film on Pre-cleaned silicon substrate by Plasma enhance Atomic Layer Deposition (PEALD) system & Elemental confirmation of deposited high-k film by using FTIR spectroscopy	A2	A1	A5	A4	A3
Post Deposition Annealing (PDA) by Rapid Thermal Annealing on deposited high-k, Metallization (Al) by Thermal Evaporation System and Post Metallization Annealing (PMA) by RTP	A3	A2	A1	A5	A4
Electrical characterization of fabricated Al/ La_2O_3 /Si MOS Device by using IV/CV setup	A4	A3	A2	A1	A5
Deposition of oxide on Si by sol gel spin on method, Annealing and Introduction of various Lithographic steps	A5	A4	A3	A2	A1

Resource persons for the course :

❖ Prof. A. M. Mahajan (Senior Professor & Head, Dept of Electronics) Having 37 yrs teaching and 20+ years independent research exp in the field of semiconductor technology, having taken exposure of working with NNIN Nanofab, UCSB, CA, USA, MDM Lab, Agrate Brianza, Itali, School of Microelectronics (collaboration) Fudan Univ., Shanghai & Dept. of Microelectronics, NCUT, Beijing, China. Established well equipped MDLN research lab (class 10000 clean room) by the way of obtaining fundings through 10 completed Major research projects and by gaining expertise in handling of fabrication and characterization equipment through 8 completed collaborative projects under INUP @ CEN, IIT Mumbai.

❖ Dr. D. J. Shirale (Assistant Professor, Dept of Electronics) Postdoc @ UCR, CA, USA having experience of using device fabrication and characterization systems in clean room and research experience of 15+ yrs in the field Nano Sensor Technology

Team of Clean Room System Operators :

- ❖ Prof. A. M. Mahajan Principal Investigator: MDLN & Class 10k Clean Lab (Overall Supervision & Monitoring)
- ❖ Dr. Sumit Patil (6+ yrs. experience of operating all the systems in MDLN lab & 10k clean room)
- ❖ Dr. Viral Barhate (5+ yrs. experience of operating all the systems in MDLN lab & 10k clean room)
- ❖ Vaibhav Borokar (4+ yrs. experience of operating all the systems in MDLN lab & 10k clean room)
- ❖ Bhushan Desale (1+ yr. experience of PEALD system operation in 10k clean room)
- ❖ Abhishek Chaudhari (1+ yrs experience of operating Thermal Evaporation and RTP Systems in 10k clean room)